

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThA2]	Nanoscale Thin Film Deposition VII
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Session Date November 13 (Thu.), 2025

Session Time 10:50-12:20

Session Room Room A (Capri Room, 2F)

[ThA2-1] [Invited] 10:50-11:20

Atomic Layer Deposition Process Development of Molybdenum Dioxide for the DRAM Capacitor Electrode Applications

Chaeyeong Hwang, Soo Min Yoo, and Woojin Jeon (Kyung Hee Univ., Korea)

[ThA2-2] [Invited] 11:20-11:40

Optimization of Atomic Layer Deposition Chemistry Toward Advanced Semiconductor Applications

Woo-Jae Lee (Pukyong Nat'l Univ., Korea)

[ThA2-3] [Invited] 11:40-12:00

Reactor-Scale Modeling and Al-Surrogate Approaches for Thin Film and Bulk Crystal Growth: Oxide ALD, Diamond MPCVD and SiC PVT

Seong-Min Jeong (KICET, Korea)

[ThA2-4] 12:00-12:20

Improved Thermal Stability and Retention in Carbon-Doped Ge₂ Sb₂ Te₅-Based Phase-Change Random Access Memory

Jisu Park, Wooseong Son, Seung Min Kang, and Changhwan Choi (Hanyang Univ., Korea)